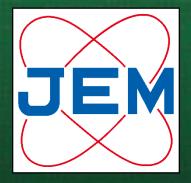


SW Test Workshop Semiconductor Wafer Test Workshop

Probing Challenges with Cu Pillar



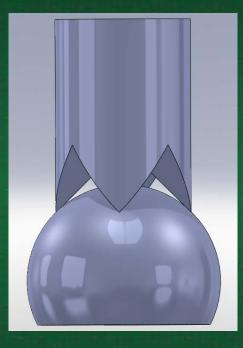
Phill Mai, JEM America Joe Mai, JEM Europe

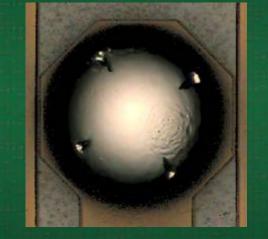
June 4-7, 2017



- Crown-tip probe limitations
- MEMS probe with flat tip
- Summary
- Future work

Crown-to-bump contact





VSCC II on Bump 150-um Z-overtravel

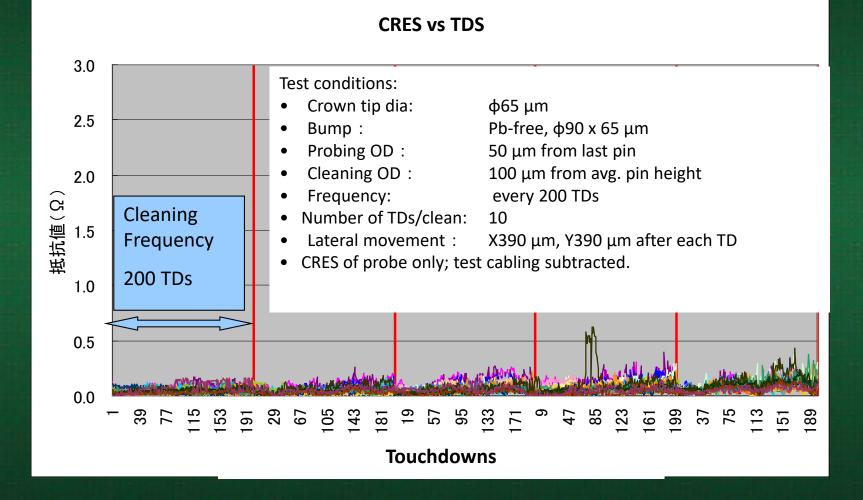
> SouthWest Test Workhsop 2005 Altera Corp / JEM / ITS

Piercing Contact

Probe mark

Abrasive/Gel Cleaning

Crown-to-bump CRES stability



Crown-to-Cu pillar contact



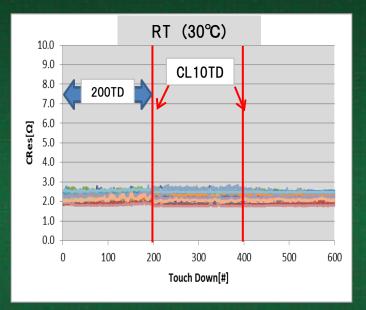
Slicing Contact

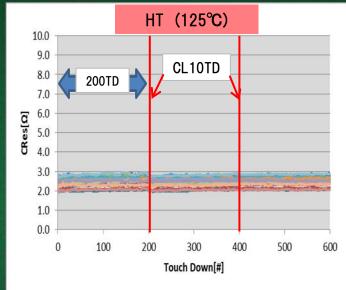
Probe mark

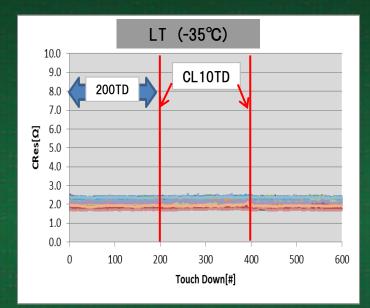
Abrasive/Gel Cleaning not so effective in the long term

Initial Crown-to-Cu pillar CRES stability

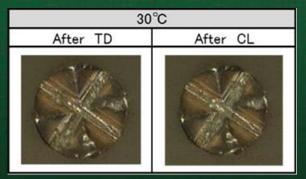
•Current: 50mA



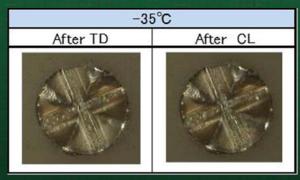




*CRES includes about 2 ohms of resistance due to PCB, Space transformer, Interposer, and probe body.

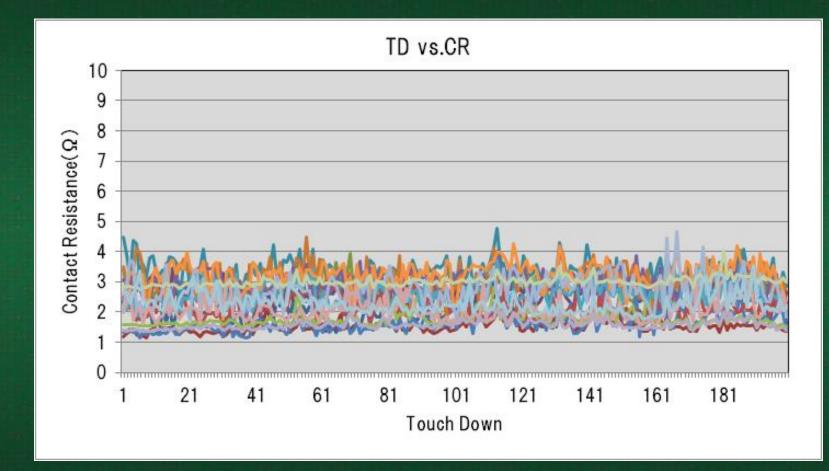




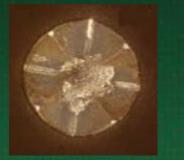


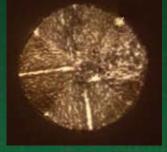
Long term Crown-to-Cu pillar CRES stability

Adhesion of SnAg causes CRES instability after 50K TDs



Crown Tip Contamination with eutectic solder



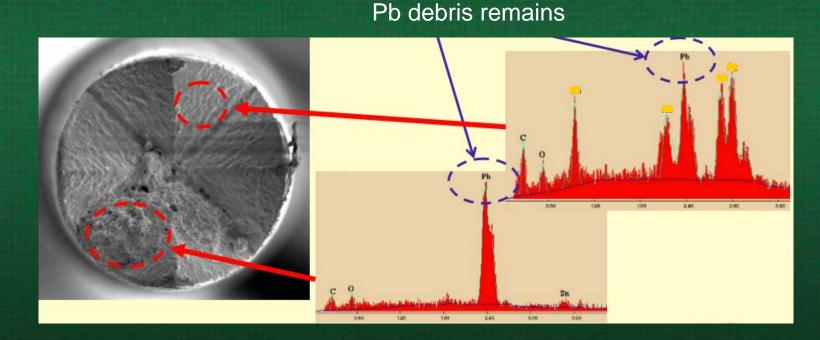


Before laser

After laser

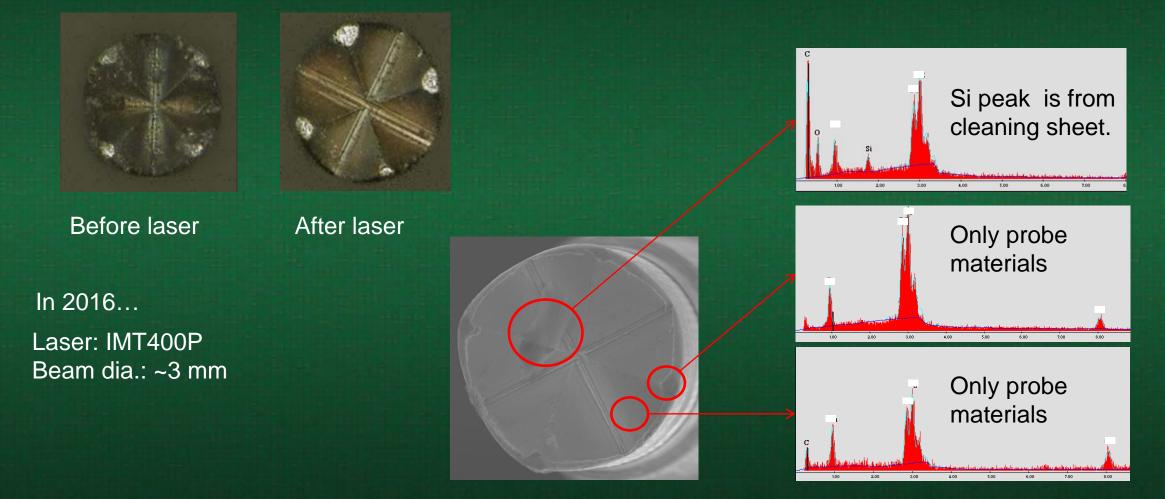
In 2007...

Laser: IMT800MV Beam dia.: ~3 mm

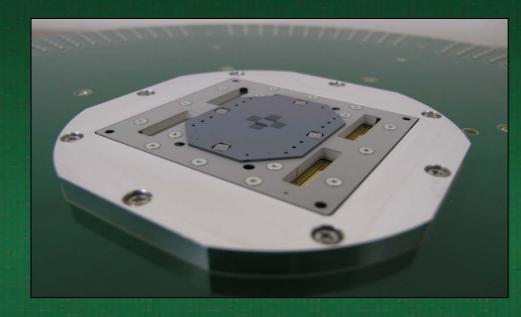


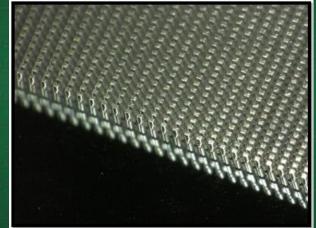
Crown Tip Contamination with Pb-free solder

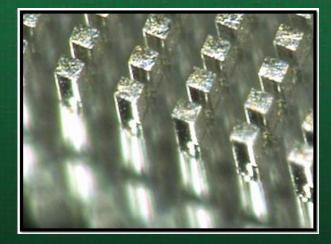
REF: "Probe Card Cleaning by Laser", J.M. Lee et.al., SWTW 2010



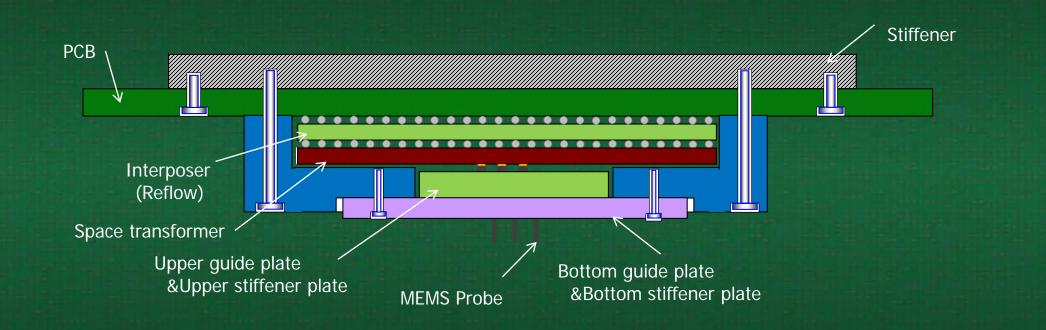
MEMS Technology (MT) as an Alternative







MT Probe Card Structure



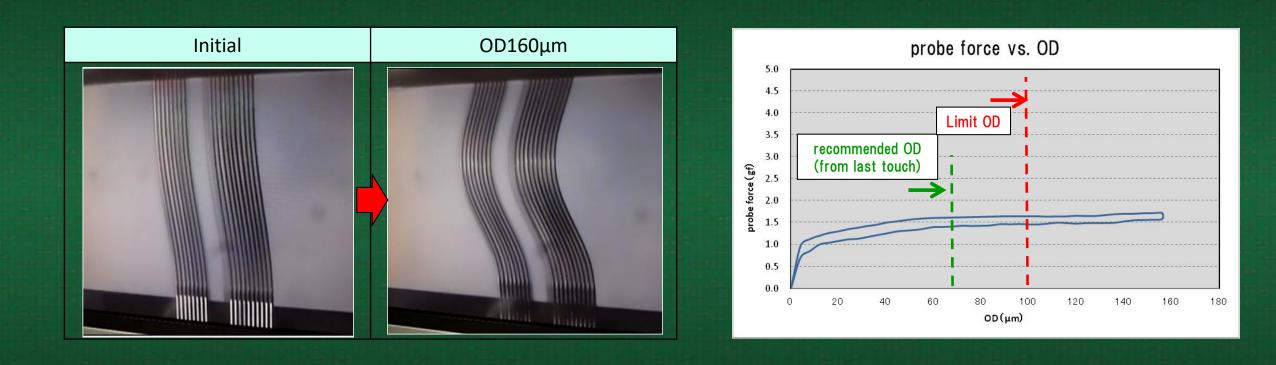
MT Probe characteristics

- Straight probe allows easy assembly and maintenance
- Composite (multi-layer) structure optimizes mechanical and electrical properties, and reduces probe wear.
- ◆ Tip material: Pd alloy



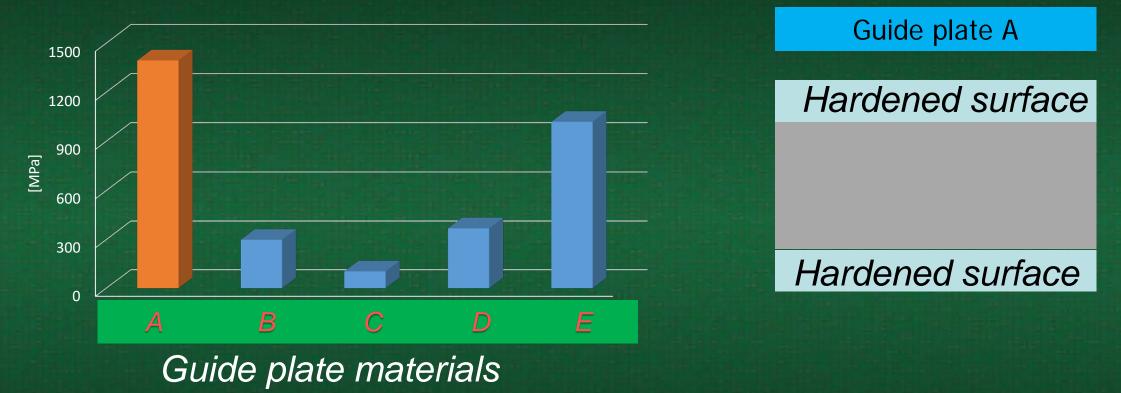


MT PROBE MECHANICS



Guide Plate Selection

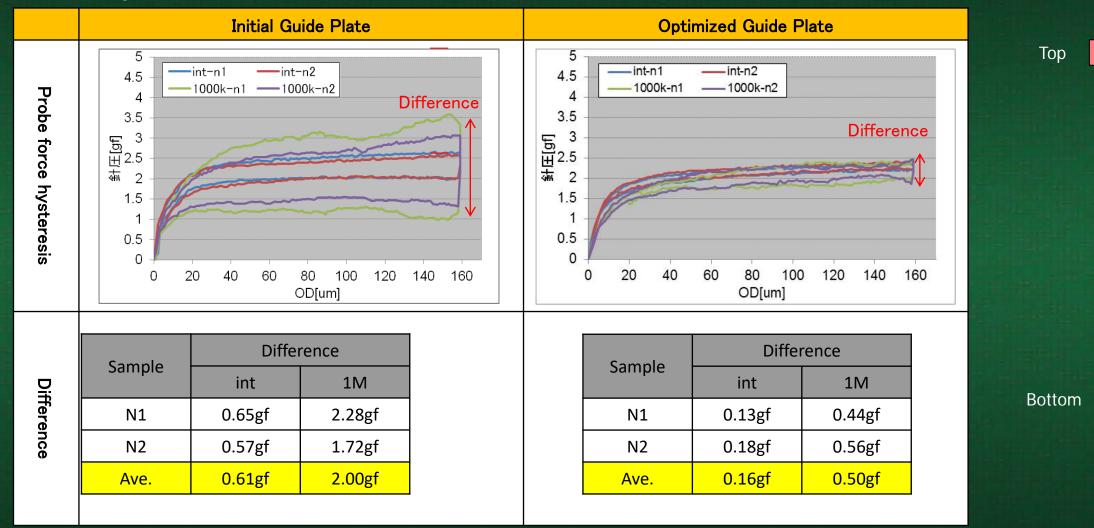
Bending Strength



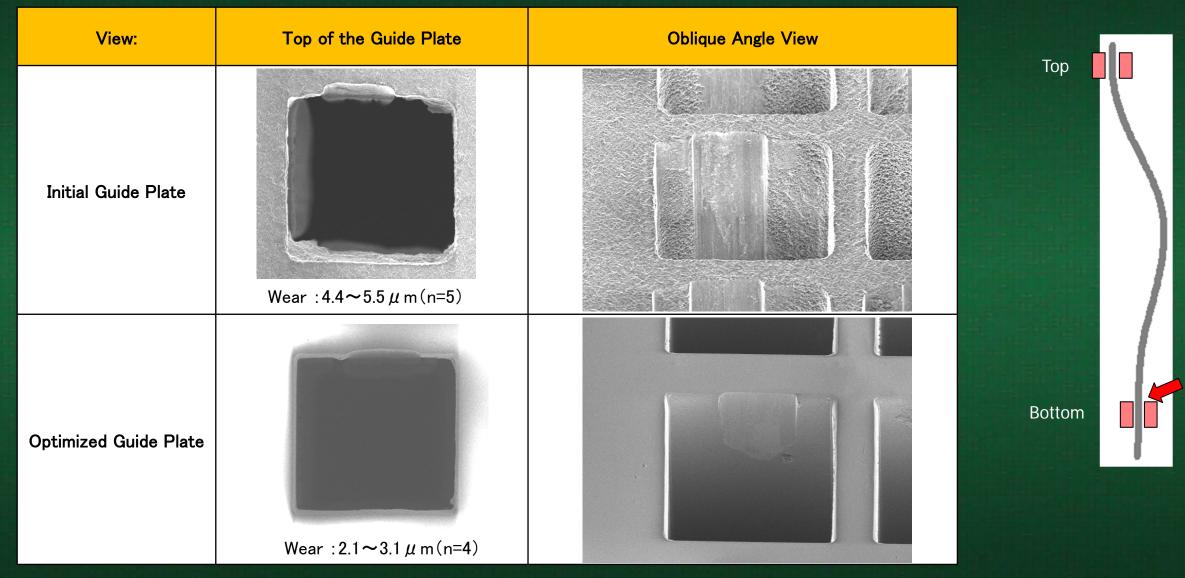
Guide plate A has high bending strength and low friction.

Probe Force Hysteresis

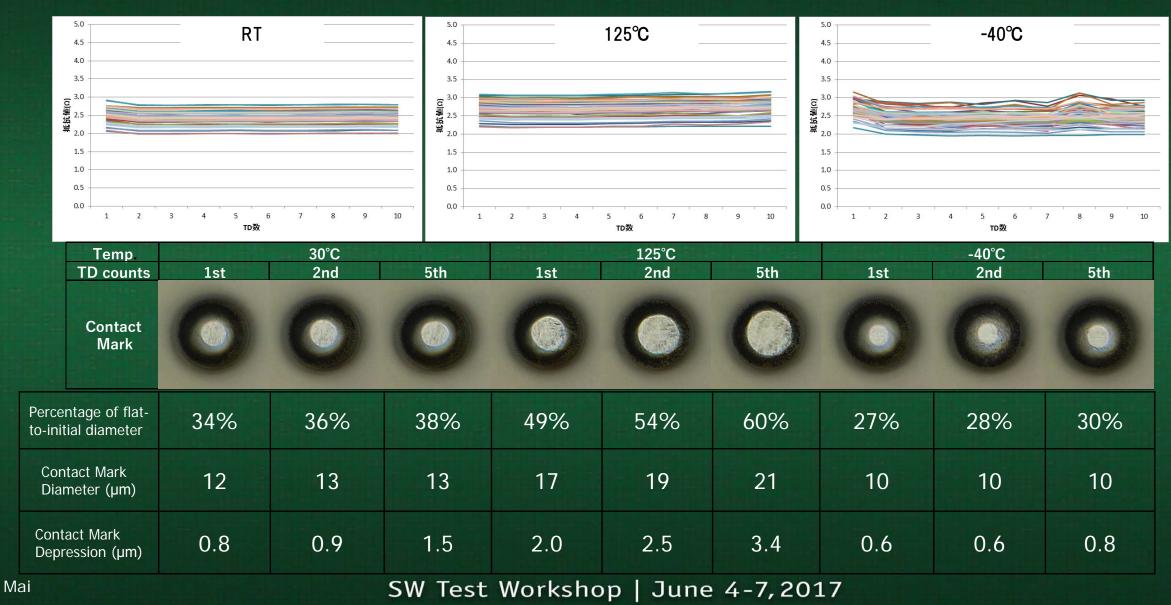
Probe : 2.5g Contact force version



Guide-plate Wear



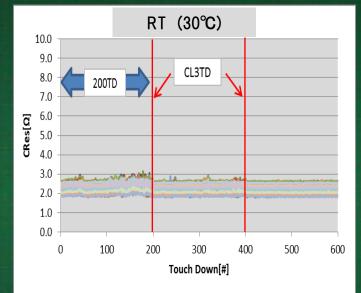
MT-to-Cu Pillar Probe Mark (multiple contacts)

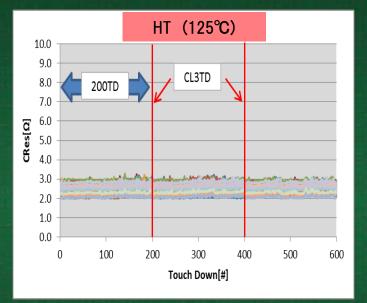


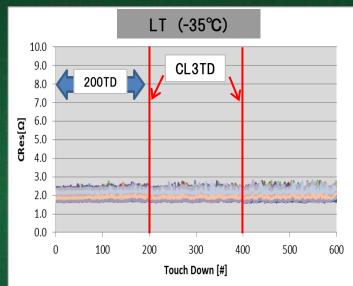
Flat-to-Cu pillar CRES Stability

Current: 50 mA

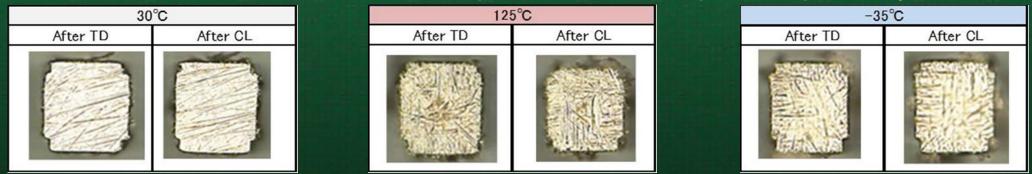
- OD: 70µm (from last pin)
- Cleaning Sheet: WA6000 lapping paper
- Cleaning Sheet OD: 70µm (from last pin)



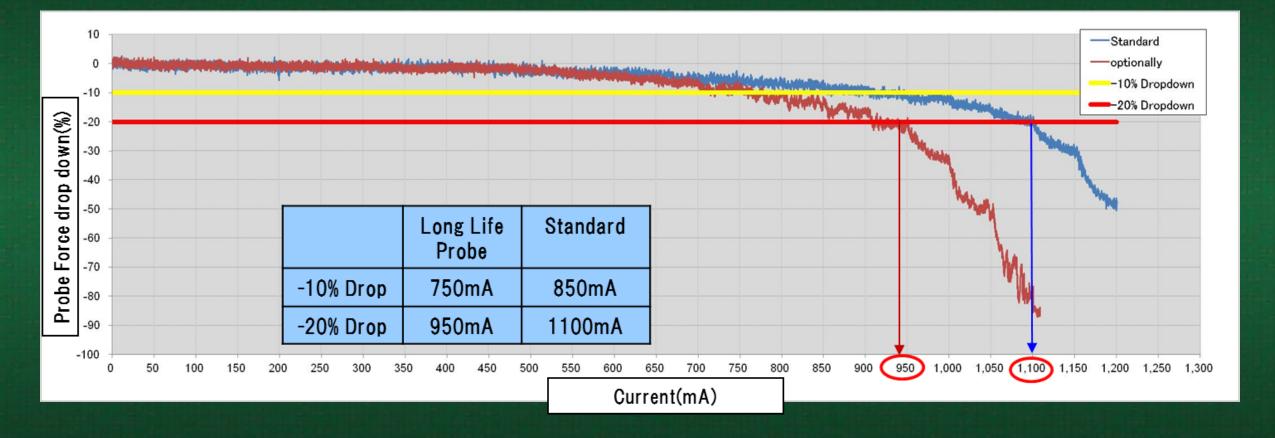




*CRes includes ~2 ohms of resistance due to PCB, Space transformer, Interposer, and probe body.

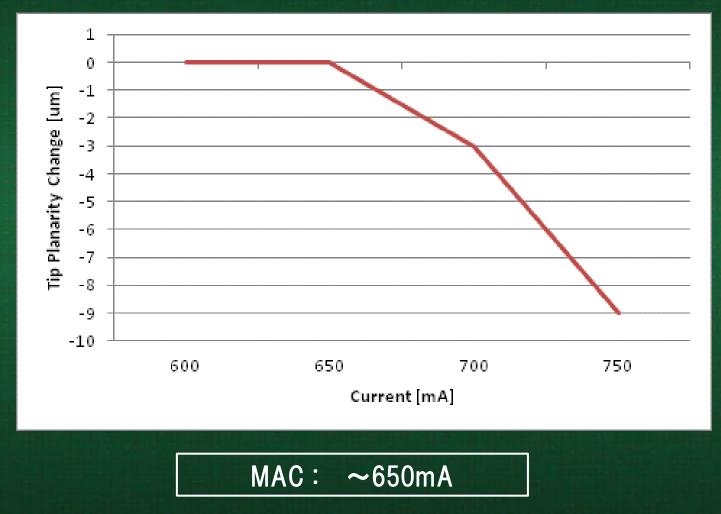


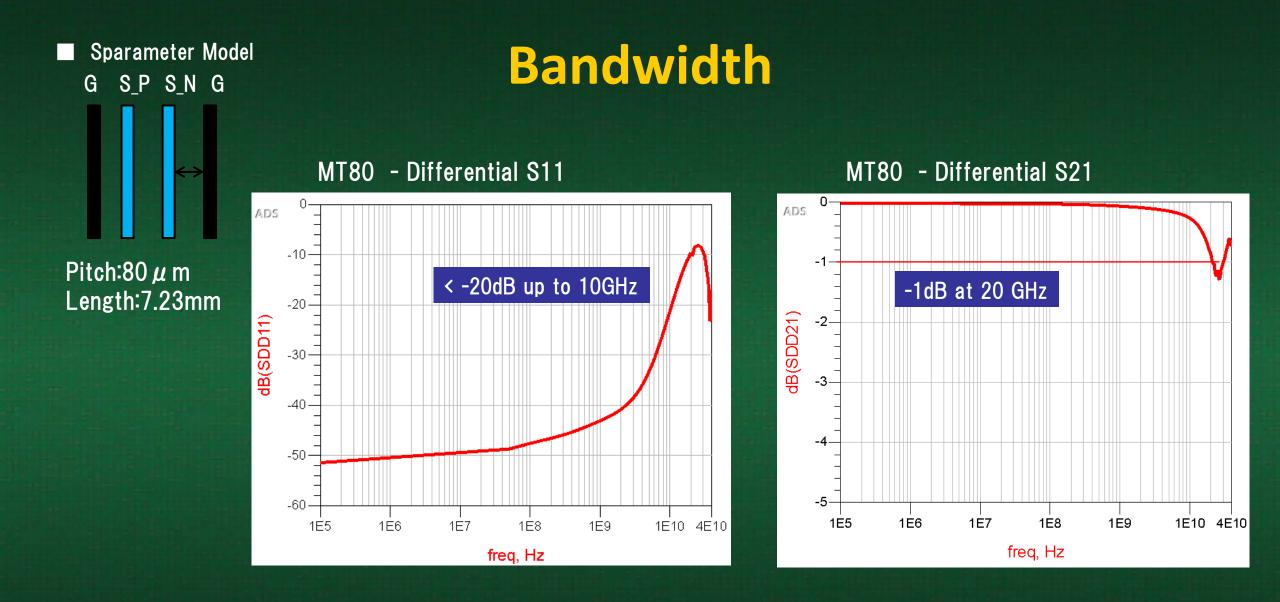
Current-Carrying Capacity (CCC)



Maximum Allowable Current (MAC)

• MT probe for 80 um pitch • Contact OD:MT 70 μ m / VS 100 μ m • Pulse:10Pulses @ 1 min-on/1 sec- off • Current: 600, 650, 700, 750mA • Number of Pins: 3 pins for MT and VS



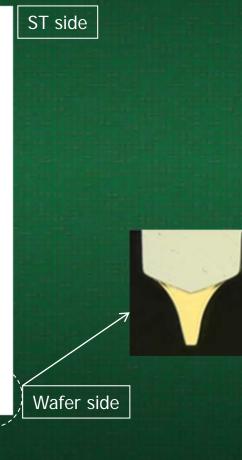




- Probing Cu pillars with minimal bump damage and stable CRES is challenging.
- Crown tips can be used, but tip cleaning is difficult and requires offline laser cleaning.
- Flat-tip MT probes are effective for probing 35 μ m dia. Cu pillars if low-friction guide plates and low probe forces are used.
- MT probes have high CCC and MAC even with small probe crosssections.

Future Work

- Develop 40um pitch MT probe.
- Increase CCC of 60-um-pitch probe to at least 500 mA.
- Develop pointed tips for Al pad contact.
- Optimize overdrive vs. temperature to minimize bump damage
- Increase max. temperature to 175 °C.



Acknowledgements

- Atsushi Mine, JEM Japan
- ITS